

10785646_CLS1.txt
Most Frequently Occurring Classifications of Patents Returned
From A Search of 10785646 on February 16, 2006

Original Classifications

2 250/548
2 356/509
2 365/36
2 524/100

Cross-Reference Classifications

5 356/401
2 128/206.24
2 250/548
2 355/53
2 356/400
2 385/129
2 385/33
2 544/209

Combined Classifications

6 356/401
4 250/548
3 355/53
2 128/206.24
2 356/400
2 356/509
2 365/36
2 385/129
2 385/33
2 430/5
2 524/100
2 544/209

Titles of Most Frequently Occurring Classifications of Patents Returned
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6 356/401 (1 OR, 5 XR)
Class 356 : OPTICS: MEASURING AND TESTING
356/399 BY ALIGNMENT IN LATERAL DIRECTION
356/401 .With registration indicia (e.g., scale)

4 250/548 (2 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/200 PHOTOCELLS; CIRCUITS AND APPARATUS
250/201.1 .Photocell controls its own optical systems
250/548 ..Controlling web, strand, strip, or sheet

3 355/53 (1 OR, 2 XR)
Class 355 : PHOTOCOPYING
355/18 PROJECTION PRINTING AND COPYING CAMERAS
355/53 .Step and repeat

2 128/206.24 (0 OR, 2 XR)
Class 128 : SURGERY
128/200.24 RESPIRATORY METHOD OR DEVICE
128/206.21 .Face mask covering a breathing passage
128/206.24 ..Mask/face sealing structure

2 356/400 (0 OR, 2 XR)
Class 356 : OPTICS: MEASURING AND TESTING
356/399 BY ALIGNMENT IN LATERAL DIRECTION
356/400 .With light detector (e.g., photocell)

2 356/509 (2 OR, 0 XR)
Class 356 : OPTICS: MEASURING AND TESTING
356/450 BY LIGHT INTERFERENCE (E.G., INTERFEROMETER)
356/496 .For dimensional measurement
356/508 ..For orientation or alignment
356/509 ...Between mask and wafer

2 365/36 (2 OR, 0 XR)
Class 365 : STATIC INFORMATION STORAGE AND RETRIEVAL
365/1 MAGNETIC BUBBLES
365/35 .Guide structure
365/36 ..Ion implantation

2 385/129 (0 OR, 2 XR)
Class 385 : OPTICAL WAVEGUIDES
385/129 PLANAR OPTICAL WAVEGUIDE

2 385/33 (0 OR, 2 XR)
Class 385 : OPTICAL WAVEGUIDES
385/15 WITH OPTICAL COUPLER
385/31 .Input/output coupler
385/33 ..Lens

2 430/5 (1 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/4 RADIATION MODIFYING PRODUCT OR PROCESS OF
MAKING
430/5 .Radiation mask

2 524/100 (2 OR, 0 XR)
Class 524 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART

OF THE CLASS 520 SERIES

- 524/1 ..Adding a NRM to a preformed solid polymer or
product, preformed specified intermediate condensation
composition thereof; or process of treating or
thereof
- 524/80 ...DNRM which is other than silicon dioxide,
glass, titanium dioxide, water, halohydrocarbon,
hydrocarbon, or elemental carbon
- 524/81Organic DNRM
- 524/86Nitrogen atom as part of a hetero ring
DNRM
- 524/99Six-membered nitrogen ring, e.g.,
pyridine, etc.
- 524/100Six-membered nitrogen ring having two or
more ring nitrogen atoms
- 2 544/209 (0 OR, 2 XR)
- Class 544 : ORGANIC COMPOUNDS -- PART OF THE CLASS
532-570 SERIES
- 544/1 ..Hetero ring is six-membered having two or
nitrogen more ring hetero atoms of which at least one is
(e.g., selenazines, etc.)
- 544/180 ...Triazines
- 544/194Substituent nitrogen bonded directly to
carbon of the triazine ring
- 544/204Two substituent nitrogens bonded directly
to two carbons of the triazine ring
- 544/208Additional ring containing
- 544/209Hetero ring